

**Amendments to the Claims:**

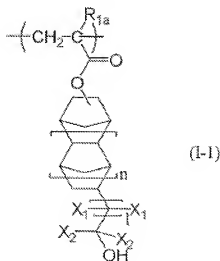
This listing of claims will replace all prior versions and listings of claims in the application.

**Listing of Claims:**

1-12. (Cancel).

13. (Previously Presented) A radiation-sensitive resin composition comprising:

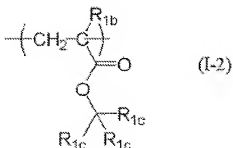
(A) a copolymer resin which comprises a recurring unit (I-1) shown by the following formula (I-1) and one or more other recurring units:



wherein  $R_{1a}$  represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms,  $X_1$  and  $X_2$  individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

(B) a photoacid generator.

14. (Previously Presented) The radiation-sensitive resin composition of Claim 13, wherein the resin (A) comprises a recurring unit (I-2) shown by the following formula (I-2):



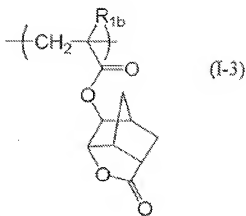
wherein  $R_{1b}$  represents a hydrogen atom or a methyl group,  $R_{1c}$  individually represents a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, or a linear or branched alkyl group having 1-4 carbon atoms, provided that (1) at least one of the  $R_{1c}$  groups is a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms, or (2) any two of the  $R_{1c}$  groups form, in combination and together with the carbon atom with which these groups bond, a divalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, with the other  $R_{1c}$  group being a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, or a linear or branched alkyl group having 1-4 carbon atoms.

15. (Previously Presented) The radiation sensitive resin composition according to Claim 14, wherein the group  $-C(R_{1c})_3$  in the formula (I-2) is an alkylcycloalkyl group.

16. (Previously Presented) The radiation-sensitive resin composition of Claim 13, wherein the content of the recurring unit (1-1) in the resin is 10-80 mol% in 100 mol% of the total recurring units forming the resin.

17. (Previously Presented) The radiation-sensitive resin composition of Claim 13, wherein the content of the recurring unit (1-1) in the resin is 10-50 mol% in 100 mol% of the total recurring units forming the resin.

18. (Previously Presented) The radiation-sensitive resin composition of Claim 13, wherein the resin (A) comprises a recurring unit (1-3) shown by the following formula (I-3):



wherein  $R_{1b}$  represents a hydrogen atom or a methyl group.

19. (Previously Presented) The radiation-sensitive resin composition of Claim 13, further comprising (C) an acid diffusion controller.

20. (Previously Presented) The radiation-sensitive resin composition according to Claim 13, wherein in formula (I-1)  $n$  is 1,  $l$  is 1, each  $X_1$  is H and each  $X_2$  is  $CF_3$ .

21. (New) The radiation-sensitive resin composition according to Claim 13, wherein the photoacid generator comprises at least one compound selected from the group consisting of 1-(4-n-butoxynaphthalen-1-yl)tetrahydrothiophenium nonafluoro-n-butanesulfonate and bis(4-t-butylphenyl)iodonium nonafluoro-n-butanesulfonate.